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Monolithic CMOS Pixel Detectors for ILC Vertex Detection

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ILC Vertex Detector Design



Monolithic CMOS Pixel Detectors

Total number

of chips 120

Layer	Radius	Total Length	No of Chips	Chip Size				
	Cm	Cm		Cm				
1	1.2	5.0	8×1	5.0x1.2				
2	2.4	25.0	8×2	12.5x2.2				
3	3.6	25.0	12×2	12.5x2.2				
4	4.8	25.0	16x2	12.5x2.2				
5	6.0	25.0	20x2	12.5×2.2				

Total Number of Pixels 1.25 x 10¹⁰

Time Structure for the Cold Design



Background Calculation:

At 1.5 cm from Interaction Point with 3 Tesla field expect 0.03 hits /mm²/bunch crossing

Will use this number for the entire detector

Conventional CCD's Not Well Suited for This Application

- Consider SLD type CCD's with 20µ x 20µ pixels
 22 mm x 125 mm = 2750 mm²
 with 6.9 x 10⁶ pixels/CCD
- Readout time at 25 MHz is 275 msec
 May be can push to 50 MHz readout or divide CCD into several readout sections
- → Can readout in 200 msec between pulse trains
- Occupancy, integrating over 2820 bunches in a pulse train
 0.03 hits/mm²/bunch x 2820 bunches x 3 pixels/hit
 = 250 pixels hit/mm²
 or 10% of the pixels have a hit (occupancy)
- SLD Experience occupancy of 10⁻³ or 2.5 hits/mm² are maximum we could handle!
- → Occupancy too high by factor of ~ 100!!

Monolithic CMOS Pixel Detectors

→What are they?

- New CMOS technology makes pixels as small as 5 μ x 5 μ possible
- Each pixel has its own intelligence (electronics) under the pixel
- Unlike CCD's, all pixels are NOT read out in a raster scan
- Reads out x,y coordinates only of pixels with hit (i.e., exceeding an adjustable threshold) at 25 MHz
- Monolithic design photosensitive detector pixel array and read out electronics for each pixel on the same piece of silicon can be quite thin (few x 100 μ ?)

Advantages over CCD's

- Significantly faster read out. Typical occupancy of vertex detector at e⁺e⁻ collider ~ 10⁻³
 1000 times faster read out! (Read only hit pixels!)
- Potentially more radiation hard
- Small 5 μ x 5 μ pixels allow good resolution
- Advantages over hybrid pixel devices used at the LHC
 - Do not need bump bonding of pixel detector to electronics layer
 - Allows much smaller pixels

Present Conceptual Design (Continued)

- Accomplish this with a Hierarchical Design Approach. Each device will have two separate sensitive pixel arrays with its own electronic logic under each pixel
 - Big Pixel (Macro Pixel or High Speed) Array
 - $50\mu \times 50\mu$ pixels
 - Triggers on hits above threshold
 - Records time of hit
 - Small Pixels (Micro Pixel or High Resolution) Array
 - $5\mu \times 5\mu$ Pixels
 - Addressable, random access array
 - Records intensity of hit (3 digit resolution)

The blue grid shows the hit big pixels

The green and yellow show the hit small pixels

If all the hit pixels come from different events the big pixel with two small pixels hit will have a two-fold bucket ambiguity

The big pixel with three hits will have a three fold ambiguity

"Event Display" showing hit pixels



50 microns

Array Designs

High-speed arrays

- Designed for quick response.
 - Threshold detection only.
 - Large pixels (~50 x 50 μ m).
- Transmits X,Y location and time stamp of impact.

High-resolution arrays

- Designed for resolution and querying.
 - Smaller pixel size (~5 x 5 μ m).
 - Random access addressability.
 - Records intensity.
- Provides intensity information only for pixel region queried.







Hierarchical Array Operation

- Particles from any particular bunch crossing traverse both the Big and the Small pixel arrays
- The Big Pixels which are hit store the time information (i.e. bunch number) in a 13 bit digital memory located under the area of the Big Pixel. The hit number counter is advanced after each hit. Up to 4 hit times can be stored under each pixel

(The probability of a Big Pixel being hit more than 4 times in a pulse train is $\leq 10^{-3}$)

• The Small Pixels which are hit store the analog signal charge locally in the area under each pixel for the duration of a pulse train

(Probability of two hits in the same Small Pixel in a pulse train is ≤ 1%)

Hierarchical Array Operation (continued)

- Readout starts in the 200 msec gap after each train
 - x,y coordinates and intensity from Small Pixels that are hit, with time stamp from the corresponding Big Pixel
 - A small fraction of the hits will have ambiguity in time, i.e., more than one time stamp

(This will increase the occupancy by 30% above 10⁻⁶)

- Both the Big Pixel and the Small Pixel arrays will be reset before the next pulse train

Macro Pixel Array Architecture



Micro Pixel Array Architecture



Expected Occupancy and Hit Rates

- Estimate for a typical 22 mm x 125 mm chip using 0.03 hits/mm²/bunch crossing (this is conservative for the outer layers). Assume that each hit will put charge above threshold into, on the average, 3 Small Pixels.
- Each chip will have
 - 22 mm x 125 mm = 2750 mm²
 - 1.1 x 10⁶ Big Pixels
 - 1.1 x 10⁸ Small Pixels
- Integrating over 2820 bunches in a pulse train we expect
 - 0.03 hits/mm²/bunch x 2820 bunches ≈ 85 hits/mm²
 - ~ 20% probability of a hit in a Big Pixel (~ 4% probability of 2 hits, 0.8% 3 hits, 0.16% 4 hits)
 - 6 x 10⁻³ occupancy in Small Pixels per pulse train
 2 x 10⁻⁶ occupancy in Small Pixels per bunch crossing
 - Effective Occupancy ~ 2 x 10⁻⁶!!
 - Total number of hits per 22 mm x 125 mm chip 7 x 10⁵ Small Pixel hits/pulse train
 - Readout time 7 x 10⁵ hits/25 MHz ~ 28 msec + some overhead

Other Comments & Issues

1. Thickness

Present state of the art is 100 to 200 μ total thickness for the sum of the Macro and Micro Arrays. Could improve with some R&D to maybe 50 μ .

2. Power Consumption

Present estimate 1.8 watts/chip could improve with R&D.

3. Fabrication Issues - two possible approaches

- a) Both Macro and Micro Pixel Arrays fabbed in a single process on the same piece of silicon.
- b) Macro and Micro Pixel Arrays fabbed in separate processes, then bonded together. No electrical connections needed between Macro and Micro Pixels in active area of detector - all connections are at one end of the chip.

4. Stitching

Present layout tooling allow 21 mm x 21 mm devices - will have to learn how to "stitch" these areas together to make our size devices. They don't think this is a problem but they have not actually done it yet in CMOS process.

5. First Prototype

- a) The first prototypes will probably be 5 mm x 5 mm devices with the readout logic on a separate chip.
- b) In the final 22 mm x 125 mm active area device the readout logic can be on the same chip, at one end, making the actual device 22 mm x 130 mm long. Output connections will be at one end (away from interaction point).

Statement of work

- Task-1 : Design and layout the micropixel (Sarnoff)
- Task-2 : Design and layout the macropixel (Sarnoff)
- Task-3 : Fabricate the test chips using MOSIS shuttle (Sarnoff)
- Task-4 : Particle bombardment on test chip (Yale/Oregon)
- Task-5 : Perform testing on test chip (Yale/Oregon w/ consulting from Sarnoff)
- Task-6 : Summarize data (Yale/Oregon/Sarnoff)
- Task-7 : Write report (Yale/Oregon/Sarnoff)



Program Plan

SARNOFF Corporation

			Q1		Q2		Q3			Q4			Q5			Q6			Q7		
ID	0	Task Name	M1	M2	M3	M4	M5	M6	M7	M8	M9	M10	M11	M12	M13	M14	M15	M16	M17	M18	M19
1		Micropixel design and layout							۹,												
2		Macropixel design and layout				-			£.												
3		MOSIS test run							Ì		 _										
4		Particle bombardment on test chips]								Ľ.										
5		Testing of chips											Č.						t.		
6		Summarize test date]																Ľ.	1	
7		Write report	1																	Ľ	

